

A cross-sectional view of a multi-layered structure. The structure consists of several horizontal layers. The bottom-most layer is labeled 102. Above it is a layer labeled 104. Above layer 104 is a layer labeled 106. Above layer 106 is a layer labeled 108. Above layer 108 is a layer labeled 110. The top-most layer is labeled 114. The layers are separated by thin lines, and the overall structure is shown in a perspective view.

FIGURE 1

2010020-00000001

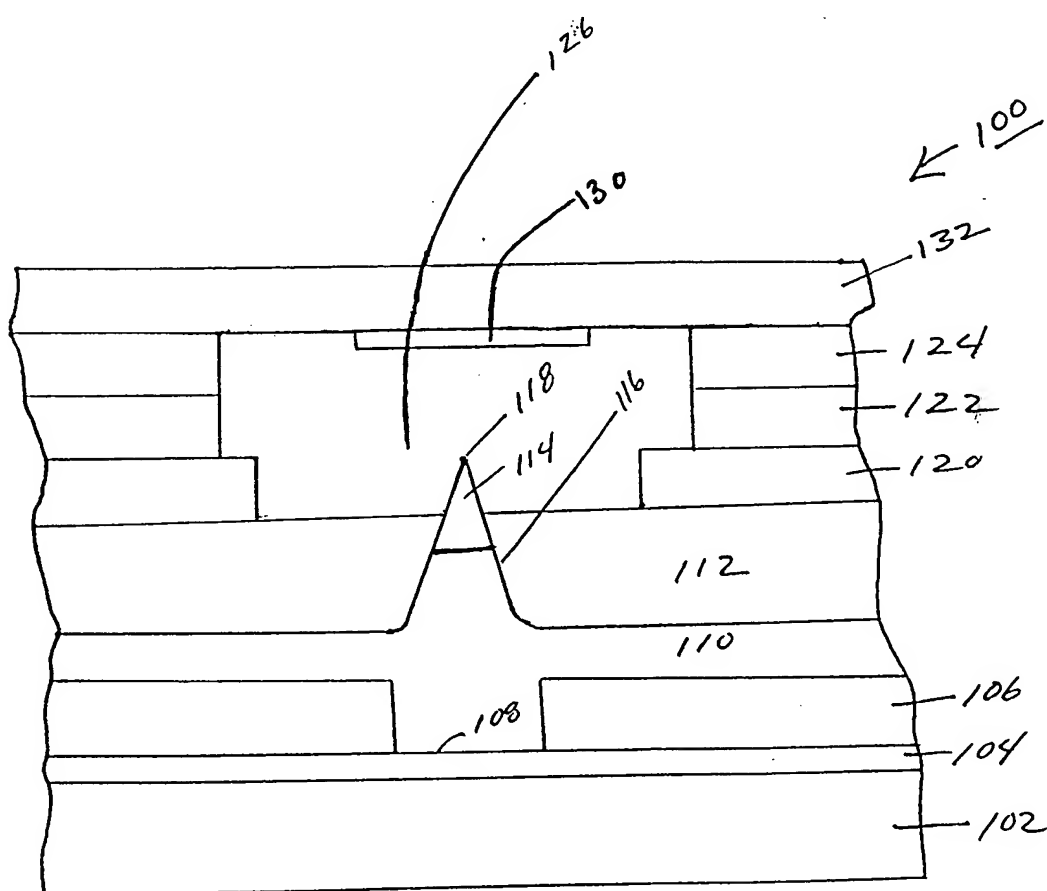


FIGURE 2

1008555 030301

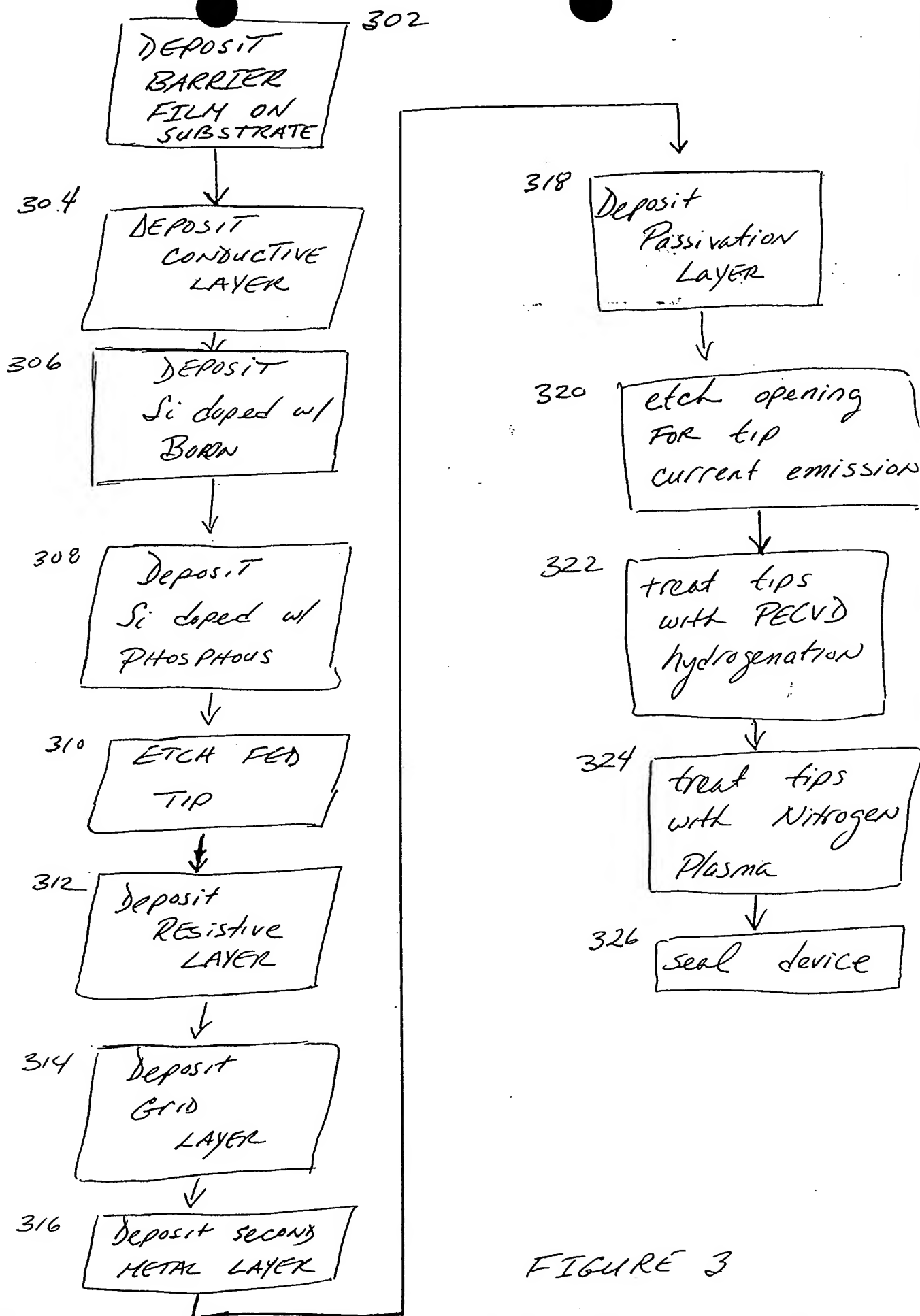


FIGURE 3

20110203 13:33:00

Surface atomic concentrations are summarized in the following table.

<i>Sample</i>	<i>O</i>	<i>N</i>	<i>Si</i>
1 (without surface treatment)	32.5	0.0	63.4
2 (with surface treatment)	20.9	33.9	34.7

FIGURE 4

201420 353303

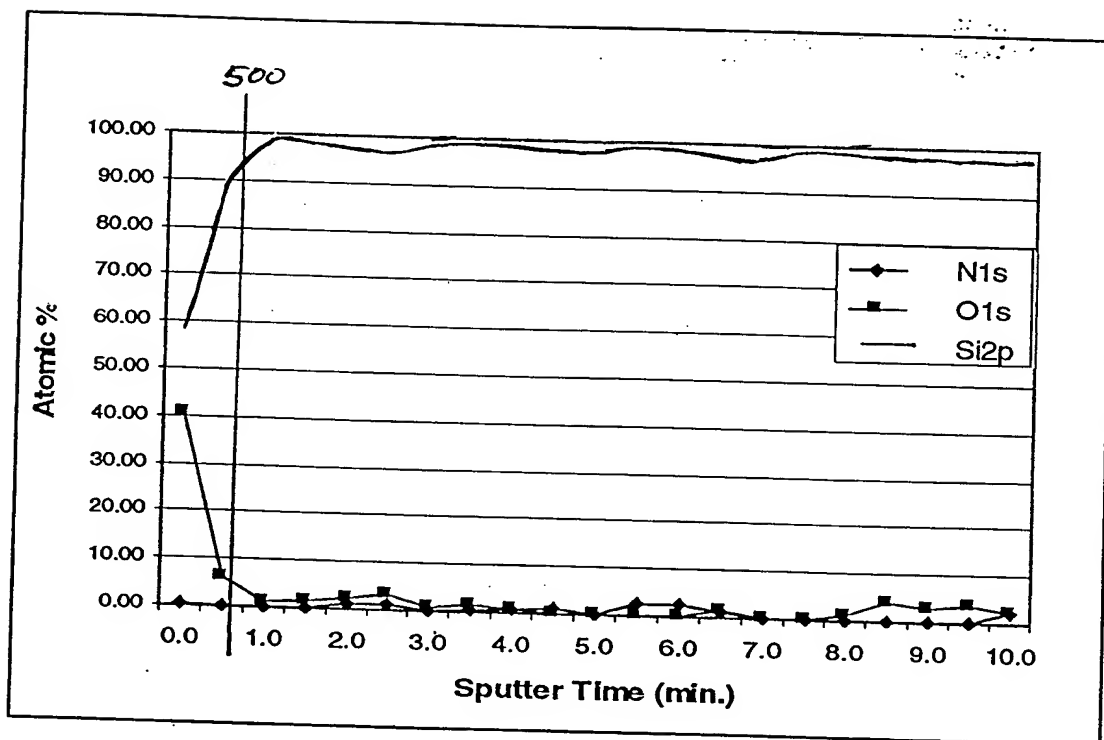


FIGURE 5

The graph displays the atomic percentage of three elements (N1s, O1s, and Si2p) as a function of sputter time. The y-axis represents Atomic % from 0.00 to 100.00. The x-axis represents Sputter Time in minutes from 0.0 to 10.0. A handwritten '600' is present above the y-axis at the 0.0 mark.

Sputter Time (min.)	N1s Atomic %	O1s Atomic %	Si2p Atomic %
0.0	35.00	19.00	45.00
0.5	28.00	9.00	63.00
1.0	19.00	2.00	79.00
1.5	12.00	1.00	87.00
2.0	8.00	0.50	91.50
2.5	4.00	0.20	95.80
3.0	2.00	0.10	97.90
3.5	1.00	0.05	98.95
4.0	0.50	0.02	99.48
4.5	0.20	0.01	99.79
5.0	0.10	0.00	99.90
5.5	0.05	0.00	99.95
6.0	0.02	0.00	99.98
6.5	0.01	0.00	99.99
7.0	0.00	0.00	100.00
7.5	0.00	0.00	100.00
8.0	0.00	0.00	100.00
8.5	0.00	0.00	100.00
9.0	0.00	0.00	100.00
9.5	0.00	0.00	100.00
10.0	0.00	0.00	100.00

FIGURE 6